

MANUFACTURING METHOD OF RECORDING MEDIUM EMPLOYING AMPHOTERIC POLYMER

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- European:

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Abstract of **JP2001180105**

PROBLEM TO BE SOLVED: To provide the manufacturing method of a recording medium employing an amphoteric polymer. SOLUTION: The recording medium constituted of at least a substrate and a coating layer provided on the substrate can be manufactured by a method wherein coating liquid, containing at least a polymer, showing hydrophilic property at a temperature lower than a transition temperature, and hydrophobic property at a temperature higher than the transition temperature reversibly while capable of forming the coating layer, is prepared and is applied on the substrate at a temperature lower than the transition temperature, then, the substrate is heated at a temperature higher than the transition temperature thereafter.

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